

<b>FORM 1449*</b> <b>SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT</b>  <b>IN AN APPLICATION</b>  (Use several sheets if necessary)	Docket Number: STFD.071US	Application Number: 10/590,223
	Applicant: LIU <i>et al.</i>	
	Filing Date: Aug. 21, 2006	Group Art Unit: 2812

U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
/S.M./	6,897,471	5/24/2005	SOREF <i>et al.</i>			
/S.M./	6,946,318	9/20/2005	WADA <i>et al.</i>			

  

FOREIGN PATENT DOCUMENTS						
	DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
	WO2005/094254	13/10/2005	WIPO			

  

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
/S.M./	2006	S. Balakumar <i>et al.</i> "Fabrication Aspects of Germanium on Insulator from Sputtered Ge on Si-Substrates." <i>Electrochemical and Solid-State Letters</i> . Vol. 9, No. 5, p. G158-G160 (2006).
	1984	R. Balasubramanian <i>et al.</i> "Fluid Motion in the Czochralski Method of Crystal Growth." <i>PCH/PhysicoChemical Hydrodynamics</i> . Vol. 5, No. 1, 1984, p. 3-18. <u>ABSTRACT ONLY</u>
	2003	Y. Ishikawa <i>et al.</i> "Strain-Induced Band Gap Shrinkage in GE Grown on Si Substrate." <i>Applied Physics Letters</i> . Vol. 82, No. 13, p. 2044-2046 (March 31, 2003).
	2004	O. I. Dosunmu <i>et al.</i> "Resonant Cavity Enhanced Ge Photodetectors for 1550 nm Operation on Reflecting Si Substrates." <i>IEEE Journal of Selected Topics in Quantum Electronics</i> . vo. 10, No. 4, p. 694-701 (July-Aug 2004).
	2005	Y. H. Kuo <i>et al.</i> "Strong quantum-confined Stark effect in germanium quantum-well structures on silicon." <i>Nature</i> . Vo. 437, No. 27, p. 1334-1336 (27 Oct. 2005).
/S.M./	1996	M. V. Fischetti <i>et al.</i> "Band structure, deformation potentials, and carrier mobility in strained Si, Ge, and SiGe alloys." <i>Journal of Applied Physics</i> . Vol. 80, No. 4, p. 2234-2252 (15 Aug. 1996).

EXAMINER /Savitri Mulpuri/ (08/26/2008)	DATE CONSIDERED
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form for next communication to the Applicant.	